

L Number	Hits	Search Text	DB	Time stamp
1	50	438/239,240,243,250,253,393,396.ccls. and capacitor and metal adj precursor	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 14:56
2	48	438/239,240,243,250,253,393,396.ccls. and capacitor and metal adj precursor and tantalum	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 14:59
3	26	438/239,240,243,250,253,393,396.ccls. and capacitor and (metal adj precursor same tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:02
4	0	438/239,240,243,250,253,393,396.ccls. and capacitor and ((metal adj precursor) same (tantalum adj alkoxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:05
5	1	438/239,240,243,250,253,393,396.ccls. and capacitor and ((metal adj precursor) same (tantalum adj ethylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:26
6	0	438/239,240,243,250,253,393,396.ccls. and capacitor and ((metal adj precursor) same (tantalum adj ethylate)) and (adsorbing same tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:28
7	0	438/239,240,243,250,253,393,396.ccls. and capacitor and ((metal adj precursor) same (tantalum adj ethylate)) and (adsorption same tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:31
8	0	257/532.ccls. and capacitor and ((metal adj precursor) same (tantalum adj ethylate)) and (adsorption same tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:36
9	0	257/528,532,533.ccls. and capacitor and ((metal adj precursor) same (tantalum adj ethylate)) and (adsorption same tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/06 15:36
-	167	(liquid adj (photoresist or resist or photosensitivity)) and ((carrier adj gas) or (inert adj gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/27 18:03
-	90	(liquid adj (photoresist or resist or photosensitivity)) and ((carrier adj gas) or (inert adj gas)) and (drying or evaporation or curing) and solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/27 18:05
-	60	(liquid adj (photoresist or resist or photosensitivity)) and ((carrier adj gas) or (inert adj gas)) and (drying or evaporation or curing) and solvent and (peeling or adhesion)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/27 18:06
-	29	(liquid adj (photoresist or resist or photosensitivity)) and ((carrier adj gas) or (inert adj gas)) and (drying or evaporation or curing) and solvent and (peeling or adhesion) and cooling	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/27 18:06
-	29	(liquid adj (photoresist or resist or photosensitivity)) and ((carrier adj gas) or (inert adj gas)) and (drying or evaporation or curing) and solvent and (peeling or adhesion) and cooling and heating	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/27 18:06